

**AMENDMENTS TO THE ABSTRACT:**

Please amend the abstract as follows:

~~The present invention is a processing method of particulate dust in plasma, in which the~~  
An apparatus for processing particulate dust in plasma is processed when a substrate ~~to be~~  
~~processed~~ is arranged in [[the]] a high vacuum enclosure, plasma is generated in the high vacuum  
enclosure, and a reactive material is appropriately introduced into the high vacuum enclosure to  
perform processing of the substrate ~~to be processed~~. At least one collecting electrode is provided  
around the substrate ~~to be processed~~ in the high vacuum enclosure other than the electrode that  
generates plasma, and particulates generated in plasma are efficiently removed by applying a  
predetermined electric potential of a direct-current or an alternating current to the collecting  
electrode, and thus a deposition problem onto an inner wall of the vacuum enclosure and a  
deterioration problem of processing accuracy and a film quality associated with flowing of the  
particulates onto the substrate are solved.

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